

Please replace the paragraph beginning at page 14, line 10, with the following rewritten paragraph:

--The gas feeder 8B may be shaped into all the peripheral portion of a cone. In this instance, the wafer boat 5 is encircled with the gas feeder 8B. The gas feeder 8B maybe shaped into a part of or all of the peripheral portion of a pyramid.--

Please replace the paragraph beginning at page 14, line 14, with the following rewritten paragraph:

--Reactant gas may be supplied to the gas feeder 8B. In this instance, the reactant gas concentration is uniform around the semiconductor wafers 5 in the wafer boat 5, and the growth rate is constant on all the semiconductor wafers regardless of the position in the wafer boat 5.--

Please replace the paragraph beginning at page 14, line 18, with the following rewritten paragraph:

--The gas feeder 8B may be incorporated in a thermal diffusion furnace. In this instance, the dopant gas concentration is uniform around all the semiconductor wafers 5, and the manufacturer achieves a target impurity profile in all the semiconductor wafers.--

IN THE CLAIMS:

Please amend claims 1 and 13 to read as follows:

1. (Amended) A gas treatment apparatus comprising:

an outer tube having a gas inlet port connected to a gas supply system for receiving gas and a gas outlet port connected to an exhaust pipe, and defining an inner space;

a wafer boat provided in said inner space and holding plural wafers spaced from one another in a predetermined direction;

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an inner tube provided between said wafer boat and said outer tube and elongated in said predetermined direction; and

ALC
a gas feeder provided between said inner tube and said wafer boat, connected to a said gas inlet port and defining a gas passage gradually reduced in cross section in said predetermined direction, and formed with a plurality of like gas outlet holes equal in open area and equally spaced in said predetermined direction for blowing said gas to said wafers.

13. (Amended) A gas treatment apparatus comprising:

ALC
an air-tight vessel having a gas inlet port connected to a gas supply system, a gas outlet port connected to an exhaust system and an inner space defined therein;

a retainer provided in said inner space and retaining plural wafers arranged at intervals; and

a gas feeder connected at one end portion thereof to said gas inlet port and having a gas passage reduced in cross section from said one end portion toward another end portion of said gas feeder and a plurality of like gas outlet holes equal in open area and equally spaced along a virtual line connected to said gas passage for blowing said gas toward said plural wafers.

IN THE DRAWINGS:

Please amend the drawings as shown in red in the attached pages.

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